933.P1/MXP/RPS/PJS

IN THE CLAIMS:

Please amend the claims as follows:

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A process chamber for processing a substrate in a process gas and reducing emissions of hazardous gas to the environment, the process chamber [gas treatment apparatus for reducing\a hazardous gas content of an effluent from a process chamber, the gas treatment apparatus] comprising:

- a support capable of supporting the substrate; <u>(a)</u>
- (b) a gas distributor capable of introducing process gas into the

process chamber;

a gas activator capable of activating the process gas to (c) perform a process in the process chamber thereby forming effluent containing hazardous gas;

(d) [(a)] an exhaust tube through which the effluent [from the process chamber] may be flowed, the exhaust tube having an internal flow surface that is substantially absent projections or recesses that alter the effluent flow path; and

(e) [(b)] a microwave energy applicator to couple microwaves to the effluent flowing through the exhaust tube\to reduce the hazardous gas content of the effluent.

The process chamber [gas treatment apparatus] of claim 1 wherein the exhaust tube comprises a length that is sufficiently long to reduce the hazardous gas content of a continuous stream of effluent flowing through the exhaust tube without recirculating the effluent in the exhaust tube.

The process chamber [gas treatment apparatus] of claim / wherein the exhaust tube comprises a length that is sufficiently long to provide a residence

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time of the effluent flowing through the exhaust tube that is at least about 0.01 seconds.

The <u>process chamber</u> [gas treatment apparatus] of claim 1 wherein the internal flow surface is adapted to provide a laminar flow of effluent through the exhaust tube.

5. The <u>process chamber</u> [gas treatment apparatus] of claim 4 wherein the exhaust tube comprises a cylinder and wherein the internal flow surface is parallel to the direction of the flow of the effluent through the exhaust tube.

The <u>process chambel</u> [gas treatment apparatus] of claim if further comprising a reagent gas mixer capable of mixing reagent gas with the effluent to further reduce the hazardous gas content of the effluent.

The <u>process chamber</u> [gas treatment apparatus] of claim 1 wherein the exhaust tube comprises monocrystalline sapphire.

8. The <u>process chamber</u> [gas treatment apparatus] of claim 1 further comprising an RF energy applicator to couple RF energy to the effluent in the exhaust tube.

The <u>process chamber</u> [gas treatment apparatus] of claim if wherein the exhaust tube comprises a distributor plate at an inlet of the exhaust tube, the distributor plate having holes adapted to direct effluent preferentially along the internal flow surface of the exhaust tube.

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A process chamber for processing a substrate in a process gas and reducing emissions of hazardous gas to the environment, the process chamber comprising:

- (a) a support capable of supporting the substrate;
- (b) a gas distributor capable of introducing process gas into the process chamber;
- (c) a gas activator capable of activating the process gas to process the substrate thereby forming effluent containing hazardous gas; [and]

 (d) an exhaust tube comprising monocrystalline sapphire
- (d) an exhaust tube comprising monocrystalline sappnire

 (through which effluent from the process chambel may be flowed; and
- (e) a microwave energy applicator adapted to couple microwaves to the effluent flowing through the exhaust tube to reduce the hazardous gas content of the effluent.

The <u>process chamber</u> [gas treatment apparatus] of claim wherein the microwave energy applicator comprises a waveguide for coupling microwaves to the effluent in the exhaust tube.

32. The <u>process chamber</u> [gas treatment apparatus] of claim 8 wherein the RF energy applicator comprises facing electrodes or an inductor coil.

REMARKS

By this amendment, claims 1-12, 14, 15 and 24-36 are pending in the application. Claims 1-9, 24, 31 and 32 have been amended. The claim amendments are supported by the specification, and no new matter is added.